



IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re the Application of

Jung-Ho LEE, et al.

Art Unit: 1712

Serial No. 10/779,733

Examiner:

Filed: February 18, 2004

Confirmation No. 2084

For: METHOD OF FORMING A SILICON OXIDE  
LAYER IN A SEMICONDUCTOR  
MANUFACTURING PROCESS

**IDENTIFICATION OF RELATED APPLICATIONS**

Commissioner for Patents  
Alexandria, VA 22313-1450

Sir:

For the record, applicant has identified in the following table all U.S. patent family members relating to the captioned application.

<u>Serial No.</u>	<u>Filing Date</u>	<u>Patent No.</u>	<u>Issue Date</u>	<u>Attv. Docket #</u>	<u>Relation</u>
09/686,624	Oct. 12, 2000	6,706,646	Mar. 16, 2004	253/006 Parent	Original Parent
09/985,615	Nov. 5, 2001	6,479,405 B2	Nov. 12, 2002	253/009	1 <sup>st</sup> CIP
10/278,992	Oct. 24, 2002			253/006 DIV	1 <sup>st</sup> Div.
10/779,733	Feb. 18, 2004			253/006 CIP.2	2 <sup>nd</sup> CIP (captioned application)

Respectfully submitted,

July 12, 2004  
Date

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### DEPOSIT ACCOUNT CHARGE AUTHORIZATION

If fee payment is enclosed, this amount is believed to be correct. However, the Director is hereby authorized to charge any deficiency or credit any overpayment to Deposit Account No. 50-1645.

Any additional fee(s) necessary to effect the proper and timely filing of the above-paper may also be charged to Deposit Account No. 50-1645.